

| L Number | Hits | Search Text | DB | Time stamp |
|----------|-------|---|-------|------------------|
| - | 19031 | (cmp or polish or polishing or planarize or planarizing) and test | USPAT | 2003/09/24 11:24 |
| - | 1653 | (cmp or polish or polishing or planarize or planarizing).ab. and test | USPAT | 2003/09/12 15:38 |
| - | 205 | ((cmp or polish or polishing or planarize or planarizing).ab. and test) and (trench or STI) | USPAT | 2003/09/12 15:39 |
| - | 1 | ((cmp or polish or polishing or planarize or planarizing).ab. and test) and (trench or STI) and (reclaim or reclaiming) | USPAT | 2003/09/12 15:39 |
| - | 193 | ((cmp or polish or polishing or planarize or planarizing).ab. and test) and (trench or STI) and semiconductor | USPAT | 2003/09/12 15:42 |
| - | 189 | ((cmp or polish or polishing or planarize or planarizing).ab. and test) and (trench or STI) and semiconductor) and @ay<=2001 | USPAT | 2003/09/15 11:31 |
| - | 3681 | (cmp or polish or polishing or planarize or planarizing).ab. and pattern | USPAT | 2003/09/15 15:07 |
| - | 1169 | ((cmp or polish or polishing or planarize or planarizing).ab. and pattern) and (trench or STI) | USPAT | 2003/09/15 11:36 |
| - | 922 | ((cmp or polish or polishing or planarize or planarizing).ab. and pattern) and (trench or STI) and ((silicon adj oxide) or SiO or SiO?sub.2 or (silicon adj dioxide)) | USPAT | 2003/09/15 15:25 |
| - | 127 | ((cmp or polish or polishing or planarize or planarizing).ab. and pattern) and (trench or STI) and ((silicon adj oxide) or SiO or SiO?sub.2 or (silicon adj dioxide))) and sacrificial | USPAT | 2003/09/15 11:58 |
| - | 1992 | ((cmp or polish or polishing or planarize or planarizing).ab. and pattern) and ((silicon adj oxide) or SiO or SiO?sub.2 or (silicon adj dioxide)) | USPAT | 2003/09/15 11:58 |
| - | 196 | ((cmp or polish or polishing or planarize or planarizing).ab. and pattern) and ((silicon adj oxide) or SiO or SiO?sub.2 or (silicon adj dioxide))) and sacrificial | USPAT | 2003/09/15 12:02 |
| - | 178 | ((cmp or polish or polishing or planarize or planarizing).ab. and pattern) and ((silicon adj oxide) or SiO or SiO?sub.2 or (silicon adj dioxide))) and sacrificial) and @ay<=2000 | USPAT | 2003/09/15 12:02 |
| - | 18 | ((cmp or polish or polishing or planarize or planarizing).ab. and pattern) and (reclaim or reclaimed or reclamation) | USPAT | 2003/09/15 13:31 |
| - | 498 | (cmp or polish or polishing or planarize or planarizing) and (reclaim or reclaiming or reclaimed or reclamation) | USPAT | 2003/09/15 13:33 |
| - | 88 | ((cmp or polish or polishing or planarize or planarizing) and (reclaim or reclaiming or reclaimed or reclamation)) and ((silicon adj oxide) or SiO or SiO?sub.2 or (silicon adj dioxide)) | USPAT | 2003/09/15 13:39 |
| - | 81 | ((cmp or polish or polishing or planarize or planarizing) and (reclaim or reclaiming or reclaimed or reclamation)) and ((silicon adj oxide) or SiO or SiO?sub.2 or (silicon adj dioxide))) and @ay<=2000 | USPAT | 2003/09/15 13:39 |
| - | 86 | (cmp or polish or polishing or planarize or planarizing).ab. and (test with pattern) | USPAT | 2003/09/15 13:54 |

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|---|------|---|-------|---------------------|
| - | 85 | ((cmp or polish or polishing or planarize or planarizing).ab. and (test with pattern)) not (((cmp or polish or polishing or planarize or planarizing) and (reclaim or reclaiming or reclaimed or reclamation)) and ((silicon adj oxide) or SiO or SiO ₂ or (silicon adj dioxide))) and @ay<=2000) | USPAT | 2003/09/15 13:54 |
| - | 74 | ((cmp or polish or polishing or planarize or planarizing).ab. and (test with pattern)) not (((cmp or polish or polishing or planarize or planarizing) and (reclaim or reclaiming or reclaimed or reclamation)) and ((silicon adj oxide) or SiO or SiO ₂ or (silicon adj dioxide))) and @ay<=2000) | USPAT | 2003/09/15 14:03 |
| - | 6 | Lacy-Michael-S.in. | USPAT | 2003/09/15 14:03 |
| - | 56 | ("3753269" "4318250" "4510113" "4576612" "4672985" "4720939" "4728552" "4753838" "4841680" "4927432" "4934102" "4954141" "4962562" "5020283" "5081051" "5104421" "5177908" "5197999" "5212910" "5234867" "5257478" "5287663" "5329734" "5335453" "5433651" "5484323" "5487697" "5489233" "5531635" "5534106" "5536202" "5547417" "5558568" "5575707" "5578362" "5593344" "5605760" "5611943" "5622526" "5643044" "5655951" "5692947" "5692950" "5725417" "5759918" "5762536" "5779526" "5810964" "5871390" "5897426" "5899798" "5908530" "5958794" "6093651" "6106351" "6206759").PN. | USPAT | 2003/09/15 14:48 |
| - | 2821 | (cmp or polish or polishing or planarize or planarizing) and sacrificial | USPAT | 2003/09/15 15:07 |
| - | 1700 | ((cmp or polish or polishing or planarize or planarizing) and sacrificial) and ((strip or stripping or remove or removing or etch or etching) with sacrificial) | USPAT | 2003/09/15 15:09 |
| - | 402 | ((cmp or polish or polishing or planarize or planarizing) and sacrificial) and ((strip or stripping or remove or removing or etch or etching) with (sacrificial near oxide)) | USPAT | 2003/09/15 15:10 |
| - | 345 | ((cmp or polish or polishing or planarize or planarizing) and sacrificial) and ((strip or stripping or remove or removing or etch or etching) with (sacrificial near oxide))) and @ay<=2000 | USPAT | 2003/09/15 15:11 |
| - | 22 | ((cmp or polish or polishing or planarize or planarizing) and sacrificial) and ((strip or stripping or remove or removing or etch or etching) with (sacrificial near oxide))) and @ay<=2000 and (test or testing) | USPAT | 2003/09/15 15:10 |
| - | 182 | ((cmp or polish or polishing or planarize or planarizing) and sacrificial) and ((strip or stripping or remove or removing or etch or etching) with (sacrificial near oxide))) and @ay<=2000 and ((trench or STI) same sacrificial) | USPAT | 2003/09/15 15:24 |
| - | 664 | (reclaim or reclaiming or reclaimed or reclamation) and semiconductor | USPAT | 2003/09/15 15:25 |

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|---|-----|--|-------|---------------------|
| - | 157 | ((re\$1claim or re\$1claiming or re\$1claimed or reclamation) and semiconductor) and ((silicon adj oxide) or SiO or SiO?sub.2 or (silicon adj dioxide) or sacrificial) | USPAT | 2003/09/15 15:26 |
| - | 147 | ((re\$1claim or re\$1claiming or re\$1claimed or reclamation) and semiconductor) and ((silicon adj oxide) or SiO or SiO?sub.2 or (silicon adj dioxide) or sacrificial)) and @ay<=2000 | USPAT | 2003/09/15 15:26 |
| - | 499 | (CMP or polishing or polish or planarize or planarizing) and (reclaim or reclaiming or reclaimed or reclamation) | USPAT | 2003/09/16 16:32 |
| - | 472 | ((CMP or polishing or polish or planarize or planarizing) and (reclaim or reclaiming or reclaimed or reclamation)) and @ay<=2000 | USPAT | 2003/09/16 16:33 |
| - | 111 | ((CMP or polishing or polish or planarize or planarizing) and (reclaim or reclaiming or reclaimed or reclamation)) and @ay<=2000) and semiconductor | USPAT | 2003/09/16 16:34 |
| - | 7 | ("3923567" "4738056" "5051375" "5131979" "5622875" "5855735" "5981301").PN. | USPAT | 2003/09/16 16:34 |
| - | 121 | (reclaim or reclaiming or reclaimed or reclamation) and (trench or STI) | USPAT | 2003/09/20 10:41 |
| - | 20 | 5622875.URPN. | USPAT | 2003/09/20 10:46 |
| - | 7 | ("3923567" "4738056" "5051375" "5131979" "5622875" "5855735" "5981301").PN. | USPAT | 2003/09/20 10:47 |
| - | 11 | 5131979.URPN. | USPAT | 2003/09/20 10:48 |
| - | 921 | (cmp or polish or polishing or planarize or planarizing) and (test near3 (pattern or structure)) | USPAT | 2003/09/24 11:30 |
| - | 591 | ((cmp or polish or polishing or planarize or planarizing) and (test near3 (pattern or structure))) and (oxide or dioxide or SiO or SiO?sub.2) | USPAT | 2003/09/24 11:27 |
| - | 591 | ((cmp or polish or polishing or planarize or planarizing) and (test near3 (pattern or structure))) and (oxide or dioxide or SiO or SiO?sub.2)) and (cmp or polish or polishing or planarize or planarizing or planarization) | USPAT | 2003/09/24 11:29 |
| - | 517 | ((((cmp or polish or polishing or planarize or planarizing) and (test near3 (pattern or structure))) and (oxide or dioxide or SiO or SiO?sub.2)) and (cmp or polish or polishing or planarize or planarizing or planarization)) and (silicon or semiconductor) | USPAT | 2003/09/24 11:29 |
| - | 87 | (((((cmp or polish or polishing or planarize or planarizing) and (test near3 (pattern or structure))) and (oxide or dioxide or SiO or SiO?sub.2)) and (cmp or polish or polishing or planarize or planarizing or planarization)) and (silicon or semiconductor)) and ((cmp or polish or polishing or planarize or planarizing) same(test near3 (pattern or structure))) | USPAT | 2003/09/24 13:17 |
| - | 15 | ("5278105" "5386088" "5652465" "5665633" "5747380" "5885856" "5923563" "5948573" "5956618" "5970238" "6087733" "6232161" "6281049" "6448630" "6486066").PN. | USPAT | 2003/09/24 11:31 |
| - | 6 | ("5736427" "6136709" "6214716" "6274483" "6297156" "6306737").PN. | USPAT | 2003/09/24 11:41 |

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|---|--------|---|-------|------------------|
| - | 3821 | (sacrifice or sacrificial) with (oxide or dioxide or SiO or SiO ₂) | USPAT | 2003/09/24 13:19 |
| - | 3043 | ((sacrifice or sacrificial) with (oxide or dioxide or SiO or SiO ₂)) and semiconductor | USPAT | 2003/09/24 13:19 |
| - | 8 | ((sacrifice or sacrificial) with (oxide or dioxide or SiO or SiO ₂)) and (re\$1claim or re\$1claiming or re\$1claimed or re\$1claimation) | USPAT | 2003/09/24 13:20 |
| - | 144 | (re\$1claim or re\$1claiming or re\$1claimed or re\$1claimation) near4 (substrate or wafer) | USPAT | 2003/09/24 13:21 |
| - | 134 | ((re\$1claim or re\$1claiming or re\$1claimed or re\$1claimation) near4 (substrate or wafer)) and @ay<=2000 | USPAT | 2003/09/24 15:06 |
| - | 1 | 6451696.pn. | USPAT | 2003/09/24 15:24 |
| - | 4 | ("3715842" "3923567" "5622875" "5855735").PN. | USPAT | 2003/09/24 15:07 |
| - | 237523 | transistor | USPAT | 2003/09/24 15:24 |
| - | 168 | transistor and (reclaim or reclaiming) | USPAT | 2003/09/24 15:24 |